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Title:

WO0009258A1: METHOD AND APPARATUS FOR TREATING WASTE GAS

CONTAINING FLUOROCHEMICALIFrench!

Derwent Title:

Decomposition of fluorine-containing compound in exhaust gas used

in etching semiconductor devices by contacting exhaust gas containing fluorine-containing compound with aluminum oxide

[Derwent Record]

[®]Country:

WO World Intellectual Property Organization (WIPO)

A1 Publ.of the Int.Appl. with Int.search report 1

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Number:

FIPC Code: B01J 21/06; B01D 53/86;

B01D53/86L; B01J21/04;

Priority Number:

1999-03-04 JP1999000056754

₹ Abstract:

A method and apparatus for decomposing a fluorochemical, e.g., C2F6, by bringing a waste gas (1) containing the fluorochemical into contact with an aluminum oxide (3), e.g., .ggr.-alumina, heated at, e.g., 800 to 900 °C. H2 may be present therein in an amount sufficient for converting the fluorine atoms of the fluorochemical to HF. The fluorochemical can be decomposed to a high degree. The aluminum oxide has a long life, and CO generation is little. [French]

[Japanese]

§ Attorney, Agent

SHAMOTO, Ichio;

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₱ Designated

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2	<u>US6790421</u>	2004-09-14	Mori; Yoichi	 Method for treating exhaust gas containing fluorine-containing compou
 2	<u>US6764666</u>	2004-07-20	Mori; Yoichi	 Process for treating gas containing fluorine-containing compounds and CC

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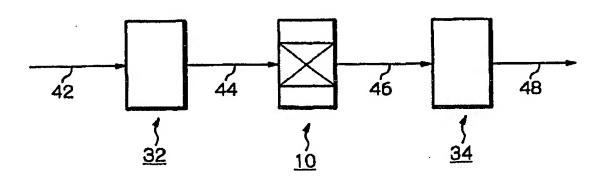
特許協力条約に基づいて公開された国際出願



WO00/09258 (51) 国際特許分類6 (11) 国際公開番号 A1 B01J 21/06, B01D 53/86 2000年2月24日(24.02.00) (43) 国際公開日 PCT/JP99/04224 (81) 指定国 JP, KR, US, 欧州特許 (DE, FR, GB) (21) 国際出願番号 (22) 国際出願日 添付公開書類 1999年8月5日(05.08.99) 国際钢查報告掛 (30) 優先権データ JΡ 1998年8月17日(17.08.98) 特願平10/244356 JР 1999年3月4日(04.03.99) 特願平11/56754 (71) 出願人(米国を除くすべての指定国について) 株式会社 荏原製作所(EBARA CORPORATION)[JP/JP] 〒144-8510 東京都大田区羽田旭町11番1号 Tokyo, (JP) (72) 発明者;および (75) 発明者/出願人(米国についてのみ) 森 洋一(MORI, Yoichi)[JP/JP] 〒253-0045 神奈川県茅ヶ崎市十間坂1-6-18-B202 Kanagawa, (JP) (74) 代理人 弁理士 社本一夫, 外(SHAMOTO, Ichio et al.) 〒100-0004 東京都千代田区大手町二丁目2番1号 新大手町ビル206区 ユアサハラ法律特許事務所 Tokyo, (JP)

(54) Title: METHOD AND APPARATUS FOR TREATING WASTE GAS CONTAINING FLUOROCHEMICAL

(54)発明の名称 フッ素含有化合物を含む排ガスの処理方法及び装置



(57) Abstract

A method and apparatus for decomposing a fluorochemical, e.g., C₂F₆, by bringing a waste gas (1) containing the fluorochemical into contact with an aluminum oxide (3), e.g., γ-alumina, heated at, e.g., 800 to 900 °C. H₂ may be present therein in an amount sufficient for converting the fluorine atoms of the fluorochemical to HF. The fluorochemical can be decomposed to a high degree. The aluminum oxide has a long life, and CO generation is little.